	Substitute Form PTO-1449 (Modified)	U.S. Department of Commerce Patent and Trademark Office	Attorney's Docket No. 07043-103001	Application No. 09/994,280
	Information Disclosure Statement by Applicant (Use several sheets if necessary)		Applicant George M. Dougherty	
			Filing Date November 26, 2001	Group Art Unit 2812

U.S. Patent Documents							
Examiner Initial	Desig. ID	Patent Number	Issue Date	Patentee	Class	Subclass	Filing Date If Appropriate
<i>RMR</i>	AA	5,651,900	07/29/1997	Keller et al.	216	56	03/07/94
<i>RMR</i>	AB	4,801,380	01/31/1989	Parket et al.	210	500.21	12/23/87
	AC						
	AD						
	AE						
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	AI						
	AJ						
	AK						

Foreign Patent Documents or Published Foreign Patent Applications								
Examiner Initial	Desig. ID	Document Number	Publication Date	Country or Patent Office	Class	Subclass	Translation	
							Yes	No
	AL							
	AM							
	AN							
	AO							
	AP							

Other Documents (include Author, Title, Date, and Place of Publication)		
Examiner Initial	Desig. ID	Document
<i>RMR</i>	AQ	Wen-Hwa Chu; Ferrari, M.; "Silicon Nanofilter with Absolute Pore Size and High Mechanical Strength"; 1995; SPIE-Int. Soc. Opt. Eng., Vol. 2593, p. 9-20
<i>RMR</i>	AR	G. Kittisland; G. Stemme; "A Sub-micron Particle Filter in Silicon"; 1990; Sensors and Actuators, A21-A23, pp. 904-907
	AS	
	AT	

Examiner Signature <i>Kevin N. Rouffiani</i>	Date Considered <i>1/22/2003</i>
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Patent and Trademark OfficeAttorney's Docket No.
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09/994,280**Information Disclosure Statement
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Applicant
George M. DoughertyFiling Date
November 26, 2001Group Art Unit
2812

(37 CFR §1.98(b))

U.S. Patent Documents

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	AN							
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Other Documents (include Author, Title, Date, and Place of Publication)

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PMR	AQ	S. Sugiyama, T. Suzuki, K. Kawahata, K. Shimaoka, M. Takigawa, and I. Igarashi, "Micro-diaphragm Pressure Sensor," Proc. IEEE International Electron Devices Mtg., Los Angeles, CA, December 7-10 1986, pp. 184-7.
PMR	AR	C.H. Mastrangelo and R.S. Muller, "Vacuum-sealed Silicon Micromachined Incandescent Light Source," Proc. IEEE International Electron Devices Mtg., San Francisco, CA, December 3-6 1989, pp. 503-6.
PMR	AS	M.W. Judy and R. T. Howe, "Polysilicon Hollow Beam Lateral Resonators," Proc. Of the IEEE Micro Electro Mechanical Systems Workshop, Ft. Lauderdale, FL, Feb. 1-10, 1993, pp. 265-271.

Examiner Signature

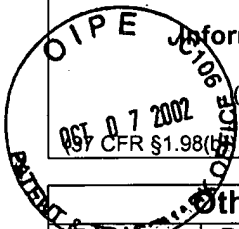
Paulo N. Rouche, Jr.

Date Considered

1/28/2003

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RNR	AT	K.S. Lebowitz, R.T. Howe, and A.P. Pisano, "Permeable Polysilicon Etch-Access Windows for Microshell Fabrication," Proc. Of the 8 th International Conference on Solid-State Sensors and Actuators (Transducers '95), IEEE Stockholm, Sweden, June 25-29, 1995, vol. 1, pp. 224-7.
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RNR	AV	Y. Kageyama, T. Tsuchiya, H. Funabashi, and J. Sakata, "Resonating Micro Structures in Microshells with HF Permeable Polycrystalline Silicon and Vacuum Sealing Thin Films," Proc. Of the 10 th International Conference on Solid-State Sensors and Actuators (Transducers '99), IEEE, pp. 340-3.
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RNR	AZ	J. Zahn, D. Trebotich and D. Liepmann, "Microfabricated Microdialysis Microneedles for Continuous Medical Monitoring," Proc. First Annual IEEE-EMBS Conf. On Microtech. In Med. And Biology, October 12-14, 2000, Lyon, France, pp. 375-380.
RNR	AAA	V.K. Mathews, "Effect of Processing Conditions on the Surface Morphology of Thin Polysilicon Films Used for DRAM Cell Capacitors," Phase Transformation Kinetics in Thin Films, Materials Research Society Proc. Vol. 230, 1992, pp. 207-212.
RNR	ABB	H. Watanabe, N. Aoto, S. Adachi, and T. Kikkawa, "Device Application and Structure Observation for Hemispherical-grained Si," J. Appl. Phys. 71, no. 7, April 1, 1992, pp. 3538-43.
RNR	ACC	H. Watanabe, A. Sakai, T. Tatsumi, and T. Niino, "Hemispherical Grain Silicon for High Density DRAMS," Solid State Technology, July 1992, pp. 29-33.
RNR	ADD	E.G. Lee and S.K. Rha, "A Study of the Morphology and Microstructure of LPCVD Polysilicon," J. of Materials Sci. vol. 28, 1993, pp. 6279-6284.
RNR	AEE	A. Banerjee, R. L. Wise, D.L. Crenshaw, R.B. Khamankar, and H. Edwards, "Evolution of Texture and Microstructure in Rough Polycrystalline Silicon for Advanced DRAM Applications," Polycrystalline Thin Films - Structure, Texture, Properties and Applications, Materials Research Society Proc. Vol. 472, 1997, pp. 433-8.
RNR	AFF	P. Krulevitch, R.T. Howe, G.C. Johnson, and J. Huang, "Stress in Updoped LPCVD Polycrystalline Silicon," Proc. Of the International Conference on Solid-State Sensors and Actuators (Transducers '91), IEEE, pp. 949-952.
RNR	AGG	P. Krulevitch, T.D. Nguyen, G.C. Johnson, R.T. Howe, H.R. Wenk, and R. Gronksy, "LCVD Polycrystalline Silicon Thin Films: The Evolution of Structure, Texture, and Stress," Evolution of Thin Film and Surface Microstructure, Materials Research Society Proc. Vol. 202, 1991, pp. 167-172.

Examiner Signature <i>Reuko N. Roufiani</i>	Date Considered 1/22/2003
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<i>RAW</i>	AHH	P. Krulevitch, G. C. Johnson, and R.T. Howe, "Stress and Microstructure in Phosphorous Doped Polycrystalline Silicon," Smart Materials Fabrication and Materials for Micro-Electro-Mechanical Systems, Materials Research Society Proc. Vol. 276, 1992, pp. 79-84.
<i>RAW</i>	AII	C. L. Yu, P.A. Flynn, S. H. Lee and J.C.Bravman, "Stress and Microstructural Evolution of LPCVD Polysilicon Thin Films During High Temperature Annealing," Thin Films - Structure and Morphology, Materials Research Society Proc. Vol. 441, 1997, pp. 403-8.
<i>RAW</i>	AJJ	G.L. Olson and J.A. Roth, "Kinetics of Solid Phase Recrystallization in Amorphous Silicon," Mat. Sci. Reports, vol. 3, no. 1, June 1988 pp. 1-78.

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